

Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

1. (Currently Amended) A positive tone radiation-sensitive resin composition comprising:

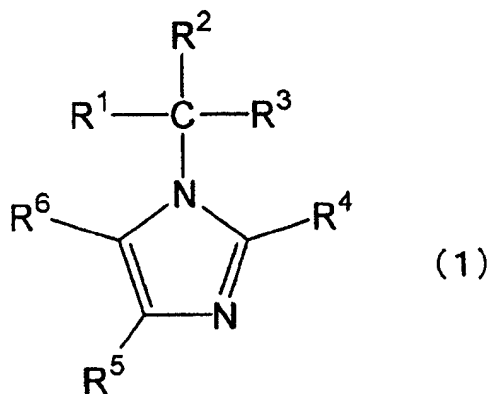
(A) compound shown by the following formula (1),

(B) a photoacid generator, and

(C) the following component (C-a) or (C-b),

(C-a) a resin protected by an acid-dissociable group, insoluble or scarcely soluble in alkali, but becoming soluble in alkali when the acid-dissociable group dissociates or

(C-b) an alkali-soluble resin and an alkali solubility controller[.],



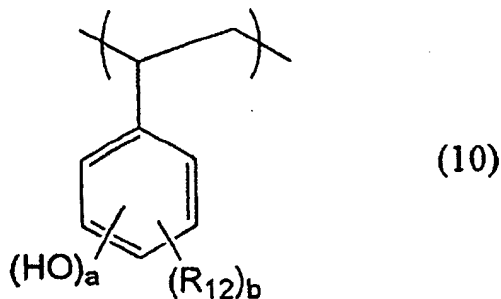
wherein R¹, R², R³, R⁴, R⁵, and R⁶ individually represent a hydrogen atom, cyano group, substituted or unsubstituted alkyl group having 1-20 carbon atoms, substituted or unsubstituted alicyclic group having 3-20 carbon atoms, substituted or unsubstituted alkenyl group having 2-20 carbon atoms, substituted or unsubstituted aryl group, or substituted or unsubstituted heteroaryl group, provided that any two groups selected from

R^1 , R^2 , R^3 , R^4 , R^5 , and R^6 may be bonded together to form a ring which may comprise a hetero atom or may bond together to form a dimer.

2. (Original) The radiation-sensitive resin composition according to claim 1, wherein the photoacid generator (B) is at least one compound selected from the group consisting of onium salt compounds, sulfone compounds, sulfonate compounds, sulfonimide compounds, diazomethane compounds, disulfonylmethane compounds, and oximesulfonate compounds.

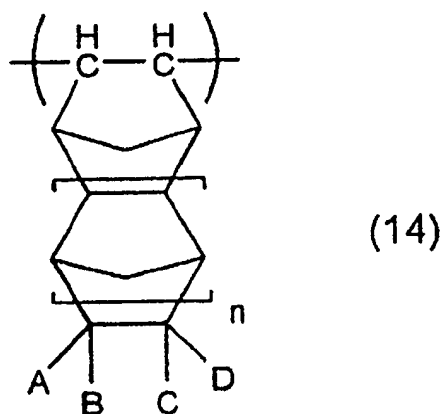
3. (Original) The radiation-sensitive resin composition according to claim 1, wherein the photoacid generator (B) is at least one compound selected from the group consisting of onium salt compounds and oximesulfonate compounds.

4. (Original) The radiation-sensitive resin composition according to claim 1, wherein the resin (C-a) protected by an acid-dissociable group, insoluble or scarcely soluble in alkali, but becoming soluble in alkali when the acid-dissociable group dissociates comprises a recurring unit of the following formula (10),

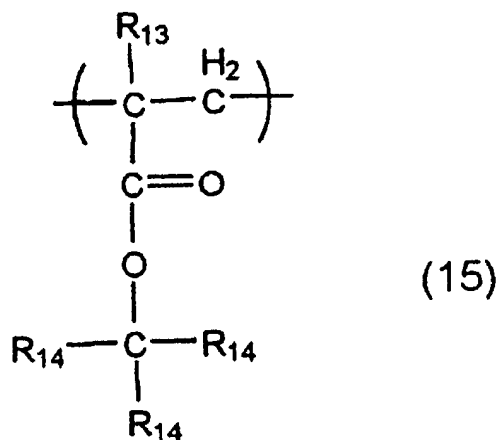


wherein R_{12} represents a hydrogen atom or monovalent organic group and a and b indicates a natural number from 1 to 3.

5. (Original) The radiation-sensitive resin composition according to claim 1, wherein the resin (C-a) protected by an acid-dissociable group, insoluble or scarcely soluble in alkali, but becoming soluble in alkali when the acid-dissociable group dissociates, comprises at least one of the recurring units of the following formulas (14) or (15),

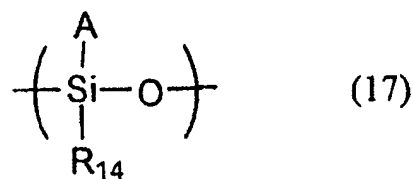
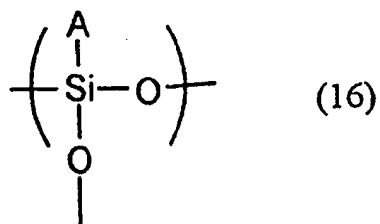


wherein A and B individually represent a hydrogen atom or an acid-dissociable group, at least one of A and B being an acid-dissociable group, D and E individually represent a hydrogen atom or a linear or branched monovalent alkyl group having 1-4 carbon atoms, and n is an integer of 0 to 2, or



wherein R_{13} represents a hydrogen atom or methyl group and R_{14} individually represents a linear or branched alkyl group having 1-4 carbon atoms or a substituted or unsubstituted monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or any two of R_{14} groups form, in combination with the carbon atom to which the two R_{14} groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms, with the remaining R_{14} group being a linear or branched alkyl group having 1-4 carbon atoms or a substituted or unsubstituted monovalent alicyclic hydrocarbon group having 4-20 carbon atoms.

6. (Original) The radiation-sensitive resin composition according to claim 1, wherein the resin (C-a) protected by an acid-dissociable group, insoluble or scarcely soluble in alkali, but becoming soluble in alkali when the acid-dissociable group dissociates, comprises at least one of the recurring units of the following formulas (16) or (17),



wherein A individually represents a monovalent organic group having an acid-dissociable group and R₁₄ represents a substituted or unsubstituted, linear, branched, or cyclic hydrocarbon group having 1-20 carbon atoms.

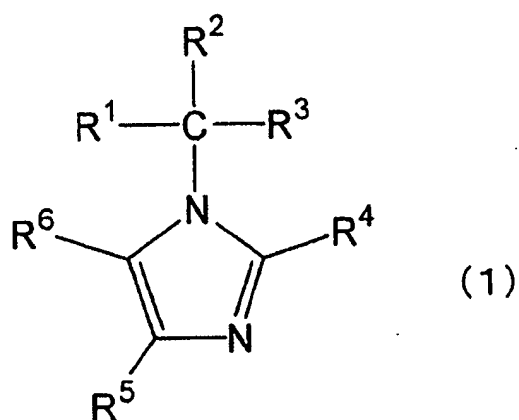
7. (Original) A negative tone radiation-sensitive resin composition comprising:

(A) compound shown by the following formula (1),

(B) a photoacid generator,

(D) an alkali-soluble resin, and

(E) a compound that can crosslink the alkali-soluble resin in the presence of an acid.



wherein R¹, R², R³, R⁴, R⁵, and R⁶ individually represent a hydrogen atom, cyano group, substituted or unsubstituted alkyl group having 1-20 carbon atoms, substituted or

unsubstituted alicyclic group having 3-20 carbon atoms, substituted or unsubstituted alkenyl group having 2-20 carbon atoms, substituted or unsubstituted aryl group, or substituted or unsubstituted heteroaryl group, provided that any two groups selected from R^1 , R^2 , R^3 , R^4 , R^5 , and R^6 may be bonded together to form a ring which may comprise a hetero atom or may bond together to form a dimer.

8. (Original) The radiation-sensitive resin composition according to claim 7, wherein the photoacid generator (B) is at least one compound selected from the group consisting of onium salt compounds, sulfone compounds, sulfonate compounds, sulfonimide compounds, diazomethane compounds, disulfonylmethane compounds, and oximesulfonate compounds.

9. (Original) The radiation-sensitive resin composition according to claim 7, wherein the photoacid generator (B) is at least one compound selected from the group consisting of onium salt compounds and oximesulfonate compounds.

10. (New) The radiation-sensitive resin composition according to Claim 1, wherein the compound (A) is selected from the group consisting of: 1-cyclohexylimidazole; 1-phenylimidazole; 1-naphtylimidazole; 1-anthrylimidazole; 1-norbornylimidazole; 1-adamantylimidazole; 1-(2'-hydroxyethyl) imidazole; 1-(3'-hydroxy-n-butyl) imidazole; 1-methoxyimidazole; 1-(2'-methyl-n-propoxy)imidazole; 1-cyanoimidazole; 1-(2'-cyanomethyl) imidazole; 1-methoxycarbonylimidazole; 1-ethoxycarbonylethoxyimidazole; 1-trifluoromethylimidazole; 1,2,4-trimethylimidazole; 1,2,4,5-tetramethylimidazole; 1,2-dihexylimidazole; 1-ethyl-2-cyclohexylimidazole; 1,2,4,5-tetracyclopentylimidazole; 1,2-dinaphthylimidazole; 1,2-dinorbornylimidazole; 1,2,4-triadamantylimidazole; 1,2,4,5-tetraethoxycarbonylimidazole; 1-cyano-2-

methylimidazole; 1-ethyl-2-methoxyimidazole; 1-(t-butoxycarbonylmethyl) imidazole; 1-(2',3'-dihydroxypropyl)-2-methylimidazole; and 1,3-di(2'-methyl-1'-imidazoylemethyl)benzene.

11. (New) The radiation-sensitive resin composition according to Claim 1, wherein the compound (A) is selected from the group consisting of: 1,2,4-trimethylimidazole; 1, 2, 4, 5-tetramethylimidazole; 1-(t-butoxycarbonylmethyl) imidazole; 1-(2',3'-dihydroxypropyl)-2-methylimidazole; and 1,3-di(2'-methyl-1'-imidazoylemethyl)benzene.

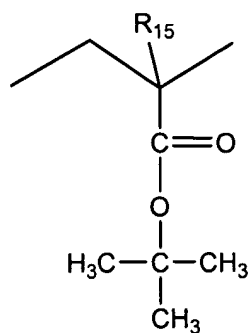
12. (New) The radiation-sensitive resin composition according to Claim 1, wherein at least one of R^5 and R^6 are not a hydrogen atom.

13. (New) The radiation-sensitive resin composition according to Claim 1, wherein R^4 is a cyano group, an unsubstituted alkyl group having 6-20 carbon atoms, a substituted alkyl group having 1-20 carbon atoms, a substituted or unsubstituted alicyclic group having 6-20 carbon atoms, a substituted or unsubstituted alkenyl group having 2-20 carbon atoms, substituted or unsubstituted aryl group, or a substituted or unsubstituted heteroaryl group.

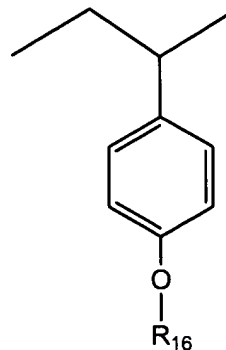
14. (New) The radiation-sensitive resin compositions according to Claim 1, wherein the photoacid generator (B) is at least one compound selected from the group consisting of onium salt compounds and diazomethane compounds.

15. (New) The radiation-sensitive resin composition according to Claim 4, wherein the resin (C-a) protected by an acid dissociable group, insoluble or scarcely soluble in alkali, but becoming soluble in alkali when the acid-dissociable group

dissociates further comprises at least one recurring unit of the following formula (10-1) or (10-2),



(10-1)



(10-2)

wherein R_{15} represents a hydrogen atom or a methyl group and R_{16} represents a 1-branched alkyl group, an alkoxy carbonyl group or a 1-substituted ethyl group.

16. (New) The radiation-sensitive resin composition according to Claim 1, wherein the composition comprises the component (C-a).

17. (New) The radiation-sensitive resin composition according to Claim 1, wherein the composition comprises the component (C-b).